<table>
<thead>
<tr>
<th>Name</th>
<th>Description</th>
<th>Price</th>
<th>Unit</th>
</tr>
</thead>
<tbody>
<tr>
<td>aln2</td>
<td>Tegal Endeavor AT sputter deposition sy</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>aml-bonder</td>
<td>AML AWB-08 Aligner Wafer Bonder</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>asap-liftoff</td>
<td>Liftoff System - Model ASAP LOM6100</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ast-ebeam</td>
<td>AST Electron Beam Dielectric Deposition</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ast-sputter</td>
<td>3” Multi-Target Reactive Co-Sputter System</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>cambridge</td>
<td>Cambridge Fiji F200 Plasma ALD</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>canon</td>
<td>Canon 4X wafer stepper</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>centura-3-5</td>
<td>Centura Compound Etch - Chamber A</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>centura-met</td>
<td>Centura DPS Metal Etcher - Ch C</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>centura-mxp</td>
<td>Centura oxide etch chamber - Ch B</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>centura-stri</td>
<td>Centura Stripper - Ch D</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>cha</td>
<td>CHA E-beam Evaporator</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>cmp</td>
<td>Strausbaugh Model 6EC CMP</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>disco</td>
<td>Disco DAD3240 Automated Dicing Saw</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ebeam1</td>
<td>Electron Beam 10 kW 4-pocket Evaporator</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>gcaps</td>
<td>GCA 3600F Pattern Generator</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>gcaws6</td>
<td>GCA 8500 5X I-line Stepper</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>gnpcmp</td>
<td>G&amp;P Poli 500 CMP</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ionmill6</td>
<td>Pi Scientific 6” Ion Beam Mill</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ksaligner</td>
<td>Karl Suss Mask Aligner MA6</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>lacvd</td>
<td>Laser Assisted Chemical Vapor Depostion</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>lam6</td>
<td>Lam 4526 Oxide Etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>lam7</td>
<td>Lam Research 9626 Aluminum Etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>lam8</td>
<td>9426 Lam Research TCP MOS Poly Etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>matrix-etch</td>
<td>Matrix 303 plasma etcher</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>mla150</td>
<td>Heidelberg Instruments MLA150 maskless aligner</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>mrc943</td>
<td>MRC Sputtering System with Sputter-etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>mrc944</td>
<td>MRC Sputtering System with Sputter-Etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxford-icp</td>
<td>Oxford Instruments PlasmaPro100 ICP65</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxford-rie</td>
<td>Oxford Plasmalab System 100</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxford2</td>
<td>Oxford Plasmalab 80 PECVD</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxfordpecvd3</td>
<td>Oxford Cluster Chamber3 PECVD</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxfordpecvd4</td>
<td>Oxford Cluster Chamber4 PECVD</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxfordpvd1</td>
<td>Oxford Cluster Chamber1 Sputter Dep</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>oxfordpvd2</td>
<td>Oxford Cluster Chamber2 Sputter Dep</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>park-afm</td>
<td>Atomic force microscope</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>picosun</td>
<td>Picosun Sunale R150 ALD</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>picotrack1</td>
<td>Picotrack Coater model PCT-200</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>picotrack2</td>
<td>Picotrack Develop model PCT-200</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>pqecr</td>
<td>Plasma Quest ECR PECVD</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>Name</td>
<td>Description</td>
<td>Price</td>
<td>Unit</td>
</tr>
<tr>
<td>------------</td>
<td>-----------------------------------------------------------------------------</td>
<td>--------</td>
<td>-------</td>
</tr>
<tr>
<td>primaxx</td>
<td>Primaxx SPTS uEtch HF Vapor Etcher</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ptherm</td>
<td>Plasmatherm reactive ion etcher</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>raman-scope</td>
<td>Laser-based Raman Spectroscopic Microscope</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>semi</td>
<td>Semigroup plasma etcher</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>sts-oxide</td>
<td>APS deep oxide etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>sts2</td>
<td>ICP pulsed gas deep silicon etch</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>svgcoat3</td>
<td>SVG 8600 6” LOR &amp; BARC Coat &amp; Bake Track</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>svgcoat6</td>
<td>SVG 6” Coat Track</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>svgdev6</td>
<td>SVG8800 6” Develop Track</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar1</td>
<td>Tystar 6” Wet/Dry Oxidation</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar10</td>
<td>Tystar LPCVD Doped Poly</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar11</td>
<td>Tystar LPCVD Doped LTO</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar12</td>
<td>Tystar Doped LTO</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar14</td>
<td>Tystar 8” LPCVD MOS Silicon Nitride, LSN, HTO</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar15</td>
<td>Tystar 8” LPCVD Doped Polysilicon</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar16</td>
<td>Tystar 8” LPCVD LTO</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar17</td>
<td>Tystar LPCVD Low Stress Nitride</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar18</td>
<td>Tystar 6” MOS Sinter</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar19</td>
<td>Tystar LPCVD Si/Ge, MOS</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar2</td>
<td>Tystar 6” Wet/Dry Oxidation</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar20</td>
<td>Tystar Si/Ge LPCVD for MEMS</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar3</td>
<td>Tystar 6” Wet/Dry Oxidation</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar4</td>
<td>Tystar 6” Wet/Dry Oxidation</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar5</td>
<td>Tystar 200mm Wet/Dry Oxidation</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar6</td>
<td>Tystar 200mm N-Type Doping</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar7</td>
<td>Tystar 200mm P-Type Doping</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>tystar9</td>
<td>Tystar LPCVD Nitride</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>ultek2</td>
<td>Ultek2 Angled Cooled Chuck E-Beam Evapor</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>xdif</td>
<td>Siemens D-5000 X-Ray Diffractometer</td>
<td>$0.96</td>
<td>minute</td>
</tr>
<tr>
<td>xetch</td>
<td>XeF2 Bulk Silicon Etcher</td>
<td>$0.96</td>
<td>minute</td>
</tr>
</tbody>
</table>